

XUV scatterometry and fluorescence for nano-structured surfaces

Frank Scholze, Anna Andrle, Analía Fernández Herrero, Anton Haase, Philipp Hönicke, Mika Pflüger, Quais Sadeeh. Victor Soltwisch



PTB, Department Radiometry with Synchrotron Radiation



Metrology with SR: Motivation





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Metrology with SR: Radiometry beyond UV



EUV-source workshop Amsterdam

Metrology with SR: Radiometry beyond UV







PTB laboratories @ BESSY I, II, MLS





since 2008: MLS



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BESSY II:

circumference 250 m electron energy 1.7 GeV

PTB:

34 m

10 beamline branches from 400 nm (3 eV) to 0.02 nm (60 keV)

Metrology Light Source MLS circumference 48 m electron energy 100 - 630 MeV 8 beamlines from 8 mm to 4 nm (300 eV)

Basic PTB capabilities: detector calibration



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Basic PTB capabilities: XUV reflectometry

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X-ray reflectometry (XRR):

Reflectance is measured as function of the incidence angle

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Basic PTB capabilities: XUV reflectometry





Avogadro constant:

$$N_A = \frac{M V r}{m}$$

m : mass M : molar mass V : volume n : atomic densitiy

Realization of a "perfect" Si crystal sphere

Determination of the number of atoms by measuring all other parameters thus determining the Avogadro constant.

By defining the value of this constant, the mass unit can be determined.

How perfect is ", perfect"? Si + $O_2 = SiO_2$!

uncertainty < 10⁻⁸ needed !

The mass (thickness) of the oxide Layer must be accurately determined

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XUV reflectometry for dimensional metrology



X-ray reflectometry: Thickness determination by interference patterns in reflectance

laboratory: Cu-K_{α}

Monochromatized SR: tunable



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New metrology challenges



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Reconstruction of Silicon nanostructures







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lamellar gratings fabricated with E-beam lithography

Pitch 50 -150 nm Linewidth 25 – 65 nm Height 25 -100 nm (etched into Si, Si3N4)

GISAXS and XUV-Scatterometry





transfer the GISAXS approach to lower photon energy (XUV) & work at steeper angle to reduce the footprint

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GISAXS scattering pattern



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Numerical precision depends on incident angle



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Reconstruction of 2D nanostructures



reconstruction examples for differently shaped laminar lines using GISAXS





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Reconstruction of 2D nanostructures

Objective function, uncertainty budget

$$\tilde{\chi}^2(E) = \sum_m \frac{\left(I_m^{\text{model}}(E) - I_m^{\text{meas}}(E)\right)^2}{\sigma^2(E)}.$$

include variation of uncertainties (maximize likelihood):

$$\log\left(\frac{1}{\sqrt{2\Pi\sigma^2}}\right) - \frac{(I_m - I_s)^2}{2\sigma^2}$$
 with (e.g.) $\sigma^2 = (ax)^2 + b^2$

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Reconstruction of 2D nanostructures





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GISAXS for small areas

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What about dense structures ?

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GISAXS: 4μm x 4 μm target 40 lines @ 100 nm pitch



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GISAXS for small areas

Just rotate a tiny bit.....



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Combined GISAXS & GIXRF





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Idea:

combine GISAXS and GIXRF in XUV spectral range

- footprint reduction
- light elements accessible
- elemental sensitive spatial distribution

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Combined GISAXS & GIXRF





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Combined GISAXS & GIXRF



Intensity variation with AoI => position sensitivity via standing wave field

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There is more.....



RDS sheets

Resonant diffuse scatter

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Resonant diffuse scatter





samples with designed roughness:

Line edge vs. line width roughness



Diffuse scatter provides information on structure => mathematics need to be developed

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Thank you for your attention











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